

Title (en)

SELF-CENTERING WAFER CARRIER SYSTEM FOR CHEMICAL VAPOR DEPOSITION

Title (de)

SELBSTZENTRIERENDES WAFERTRÄGERSYSTEM ZUR CHEMISCHEN DAMPFABSCHIEDUNG

Title (fr)

SYSTÈME DE SUPPORT DE TRANCHES À AUTO-CENTRAGE À DES FINS DE DÉPÔT CHIMIQUE EN PHASE VAPEUR

Publication

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Application

EP 16815048 A 20160610

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Abstract (en)

[origin: WO2016209647A1] A self-centering wafer carrier system for a chemical vapor deposition (CVD) reactor includes a wafer carrier comprising an edge. The wafer carrier at least partially supports a wafer for CVD processing. A rotating tube comprises an edge that supports the wafer carrier during processing. An edge geometry of the wafer carrier and an edge geometry of the rotating tube being chosen to provide a coincident alignment of a central axis of the wafer carrier and a rotation axis of the rotating tube during process at a desired process temperature.

IPC 8 full level

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